

15/1/02 16/2/02

FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary) <div style="border: 1px solid black; border-radius: 50%; padding: 5px; display: inline-block;"> MAY 15 2002 PATENT & TRADEMARK OFFICE </div>				ATTY DOCKET NO. 00862.022541		APPLICATION NO. 10/091,461	
APPLICANT MASATAKA ITO							
FILING DATE March 7, 2002						GROUP 2812	
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
SDI	5,869,387	02/09/1999	Sato et al.	438	459	03/13/1995	
SDI	6,171,982	01/09/2001	Sato	438	795	12/22/1998	
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT	
SDI	05-152230	06/18/1993	Japan			Abstract	
SDI	05-217821	08/27/1993	Japan			Abstract	
SDI	11-265893	09/28/1999	Japan			Abstract	
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)							
SDI	"Nano-Defects In Commercial Bonded SOI And SIMOX", D.K. Sadana et al., 1994 IEEE International SOI Conference Proceedings, October 1994, pp. 111-112.						
SDI	"Extremely Low Si Etching (<1nm) During Hydrogen Annealing of Silicon-on-Insulator", N. Sato et al., Extended Abstracts of the 1998 International Conference on Solid State Devices And Materials, Hiroshima, 1998, pp.298-299.						
SDI	"Suppression of Si Etching During Hydrogen Annealing of Silicon-on-Insulator" N. Sato et al., 1998 IEEE International SOI Conference Proceedings, October 1998, pp. 17-18.						
SDI	"Hydrogen Annealing Treatment Used To Obtain High Quality SOI Surfaces" H. Moriceau et al., 1998 IEEE International SOI Conference Proceedings, October 1998, pp. 37-38.						
SDI	"Defect Reduction Of Bonded SOI Wafers By Post Anneal Process In H ₂ Ambient", N. Tate et al., 1998 IEEE International SOI Conference Proceedings, October 1988, pp. 141-142						
EXAMINER <i>Stanetta deane</i>				DATE CONSIDERED <i>11/7/03</i>			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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